

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of: Confirmation Number: 7419

FUKIAGE et al.

Application No.: 10/702,049 Group Art Unit: 1792

Filed: November 6, 2003 Examiner: Tadayyon Eslami, Tabassom

Title: METHOD OF IMPROVING POST-DEVELOP PHOTORESIST PROFILE ON  
A DEPOSITED DIELECTRIC FILM

AMENDMENT AFTER FINAL REJECTION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In response to the Final Office Action dated June 12, 2008, the due date for response to which has been extended to October 12, 2008 by the attached Petition for a One Month Extension of Time and Fee, please amend the above-identified application as follows: